

HCMOS EMBEDDED ARRAY

PRELIMINARYDATA

FEATURES

- Combines Standard Cell features with Sea Of Gates time to market.
- 0.7 micron triple layer metal HCMOS process featuring self-aligned twin tub N and Pwells, low resistance polysilicide gates and thin metal oxide.
- \Box 2 input NAND (ND2P) delay of 0.25 ns (typ) with fanout $= 2$
- \blacksquare 5 V, 3.3 V and mixed voltage library versions.
- **Embedded functions for High Density SPRAM,** DPRAM, ROM and FIFO.
- \blacksquare Video DAC (3 x 8 Bit) for graphics applications at 80 or 135 MHz.
- Phase Locked Loop function for chip to chip clock management and frequency synthesis.
- Metallised functions to support SPRAM, DPRAM and ROM.
- Fully independent power and ground configurations for core and I/O cells.
- Variable I/O ring capability from 48 to 400 pads.
- Output buffers capable of driving ISA, EISA, MCA, and SCSI interface levels.
- True not pseudo TTL interface
- High drive I/O capability of sinking up to 24 mA \blacksquare (48 mA option)with slew rate control and current spike suppression.
- Active pull up and pull down devices.
- Buskeeper I/O functions.
- Oscillators for wide frequency spectrum.
- Broad range of 228 SSI and core cells. \blacksquare
- 200 element macrofunction library \blacksquare
- Design For Test includes LSSD macro library \blacksquare option for megacells and IEEE 1149.1 JTAG Boundary Scan architecture.
- Cadence based design system with interfaces п. from multiple workstations.
- Broad ceramic and plastic package range \blacksquare
- Latchup trigger current $> +/- 200$ mA.
- ESD protection $> +/- 2000$ volts \blacksquare

EMBEDDED FUNCTIONS

GENERAL DESCRIPTION

The ISB28000 EMBEDDED™ ARRAY series uses a high performance, triple level metal HCMOS process to achieve sub-nanosecond internal speeds, while at the same time, offering low power dissipation and high noise margin. The die size is variable up to 216,000 wireable 2-input NAND gates. Even higher effective utilizations are achieved with the optimization of metallised and embeddable memory megacells.

The high current I/O cell counts range from 48 to 400 full function cells. The output buffers have drive strengths capable of sinking up to 48 mA and sourcing up to 12 mA without limiting the functionality of adjoining cells. Output buffers are electrically compatible with EISA, ISA, MCA and SCSI interface standards.

The ISB28000 library is available in all 5V, all 3.3 V and a combined mixed voltage versions This allows the core and I/O to be powered from different voltage levels for an optimal combination of performance, power consumption and interface compatibility.

Testability is supported at device level withthe close coupling of the scan path flip flops, automatic test pattern generation and high pattern depth tester architectures. At the system level testability, IEEE 1149.1 JTAG is fully supported.

A wide range of CAD tools are combined into the design system allowing design development on a choice ofworkstations. An extensive package offering makes this series well suited for a broad range of high performance applications. The product technology may be used in commercial, industrial and military environments.

Figure 1. Triple Level Metal Architecture

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TECHNOLOGY OVERVIEW

The ISB28000 Series Embedded Array is an evolution of the CONTINUOUS ARRAY™ architecture with the added capability of embedded functions for the core and periphery. The embedded functions can be used for high density RAMs where performance is the prime criteria. The core is amatrix of potentially active transistors. Surrounding the core are the configurable I/O cells, and V_{DD} / V_{SS} pads occupying pre-established locations. Three levels of metal are used as shown in Figure 1. Intracell and intercell wiring are limited to first level metal with the second and third metal levels dedicated to interconnect wiring and power distribution. The reduced geometry of the ISB28000 transistors can only be used to full advantage with short interconnect between macrocells. The third level of metal greatly reduces the interconnect and increases the gate utilization to an average 75%. Further advantages include improved power dissipation and increased performance.

The basic cell is a pair of N and P channel transistors that are vertically arranged. The width of the

P channel transistor is larger than the N channel transistor thereby providing improved symmetrybetween the rise and fall times of macrocells. The basic cells are placed adjacent to each other without field isolation to form a multiple column row. Adjacent basic cells may be uniquely wired together to form a variety of macrocells. Isolation between macrocells is accomplished by placing the endmost basic cell in the cutoff state, thus providing flexibility and space efficiency. Each basic cell has 17 horizontal wiring channels on first metal,1 vertical wiring channel on second metal and 15 horizontal wiring channels on third metal.

As can be seen from Figure 2, the first metal V_{DD} and Vss power lines run horizontally on the top and bottom of each row. Every other row is flipped relative to the previous row thereby allowing the sharing of supply lines between adjacent rows. Additionally, a 2 column wide vertical power screen is provided every 36 columns on second metal.A third power screen is provided which is a replica of the first level power screen but with opposite polarity.

Figure 2. Internal Core Cell ND2

EVALUATION DEVICE

An evaluation device is used to demonstrate the performance of the ISB28000 series as well as verify the effecti-veness of the design system. The device has path delays, latches, a host of macrocells and embedded functions which were used to verify the

simulated characteristics that are supplied in the data book.Characterization of the path delays including interconnect shows typical delays of 250 ps for a 2 input NAND with receivers/drivers operating at frequencies inexcess of 100 MHz.The evaluation device is avai-lable in a 208 pin guard quad flat pack.

Figure 3. Evaluation Device

LIBRARY

The following section details the elements which make up the ISB28000 Series library. The elements are organized into three categories

1. Macrocell libary with Input, Output, Bidirectional Buffers and Core cells including JTAG macrocells.

- 2. Macrofunctions
- 3. Module Generators
- 4. Embedded Functions

I/O Buffers

The I/O buffers are located on the periphery of the array. Figure 4 is a plot of an I/O buffer. The basic cell consists of a bond pad with an input protection, an output driver section and a receiver/pre-driver section. Every I/O maybe configured as either input, output, bidirectional, tri-state output, tri-state bidirectional, or additional V_{DD}/V_{SS}. High impedance

pull-up or pull-down resistors are also available in the I/O cell resistors. Input and output macrocells do not invert logic signals. The output transistors are provided with an independent power distribution metalization thereby minimizing switching transients in the periphery from affecting either the on chip receivers or the internal matrix.

Several important features are incorporated in the output drivers. These include slew rate control and current spike suppression. Slew rate is controlled by turning on individual sections of the large output transistor in a controlled manner. During normal switching a large surge of current occurs when a conventional CMOS buffer has both P and N channel transistors in conduction. This situation is avoided by placing the buffer in tri-state for approximately 200 ps during the time the buffer changes state. Each output buffer may be configured for up to 24 mA current drive capability.

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True TTL Compatibility. The TTLbus driver buffers are designed to operate in conjunction with bipolar products on a common data bus. The output voltage swings and current drive capabilities are the same as bipolar TTL buffers. This allows the system designer to take advantage of the low power consumption of the ISB28000 array CMOS logic while not being forced to deal with pseudo TTL buffers. Most CMOS array TTL buffers are standard CMOS buffers with new delay equations.These CMOS pseudo TTL buffers display various undesired operational nets to the 5 V rail having low impedance PMOS transistors which not only slow down the net by raising the discharge time but may also damage the bipolar TTL receivers connected to the net. The ISB28000 does not pull to rail. Another problem with pseudo TTL buffers is the high impedance input

exhibited when in tri-state mode. This can cause undesired reflections on the data bus and is overcome in the ISB28000 by means of two diodes which exhibit input characteristics common to biplolar devices in tristate mode.

Standard Bus Compatibility. A subset of the TTL buffers conform to ISA, EISA, MCA and SCSI bus operating specifications. These buffers comply fully with the specification rise and fall times. Figures 5a and 5b show the D.C Specifications for True TTL Output Buffers and Input Receivers respectively.Theytarget the high performance 32 bitRISC and CISC architectures and data communication sytems. Selection of the correct output buffer is very important to achieve the desired performance. Two parameters used to select the appropriate buffer are maximum drive current and load capacitance.

Exceeding the maximum load capacitance will also result in slower switching performance. Exceeding the maximum current may result in degraded levels of reliability. Standard CMOS and TTL levels are specified for all external buffers. Schmitt Trigger input receivers are available. All buffers are designed forcommercial, industrial and military operation.

Table 1. I/O Drive capability for slew rate control buffers

Current Drive (mA)	Standard Unit	Maximum Capacitance (pF)
4.0	0.33	100
8.0	0.67	200
12.0	1.00	300
16.0	1.33	500
24.0	2.00	750

Table 2. I/O Drive capability for non-slew rate control buffers

Current Drive (mA)	Standard Unit	Maximum Capacitance(pF)
4.0	1.0	100
8.0	2.0	200
16.0	3.0	500

Table 3. Temperature and Voltage Multipliers

All pads except the eight corner pads can be configured aspower or I/O pads. The configured power pads are known as placeable pads and have an associated multiplication factor dependent on the buffer drive current capability, as shown in Table 1. the current for each type of buffer is:

IBuffer **= Buffer Current (max.) x Multiply factor x Number of Buffers**

Table 2 shows the Sink and Source current for typical buffers.

Core Logic

The propagation delays shown in the ISB28000 data book and in the AC Characteristics section of this data sheet are given for nominal processing, 5V operation, and 25°C temperature conditions. However there are additional factors that affect the delay characteristics of the macrocells. These include loading due to fanout and interconnect routing, voltage supply, junction temperature of the device, processing tolerance and input signal transition time. Prior to physical layout, the design system can estimate the delays associated with any critical path. The impact of the placement and routing can be back annotated from the layout for final simulations of critical timing.The effects of junction temperature, (K_T) and voltage supply, (K_V) on the delay numbers are summarized in Table 3. A third factor, is associated with process variation. This multiplier has a minimum of 0.6 and a maximum of 1.6.

Macrocells And Macrofunctions

The ISB28000 series has internal macrocells that are robust in variety and performance. Specialized cells for scan techniques and a mix of complex logic functions round off the SSI offering. High drive, double output power versions, which may be used to speed up critical paths, are available for most internal macrocells.

Macrofunctions are a series of soft-macros facilitating quick capture of large functional blocks and are available for such functions as counters, shift registers and adders. Macrofunctions areimplemented at layout by utilizing macrocells and interconnecting to create the logic function.

Module Generators

A series of module generators are available to support a range of megacells. These modules enable the designer to choose individual parameters in order to create a compiled cell which meets the specific application requirements.The compiled cells are implemented using a special leaf cell technique which

Table 4. Macrocell 5V Library Summary

ensures predictable layout and accurate module characteristics.

Generators are available for megacells such as single port RAM, dual port RAM and ROM. In choosing megacells the designer can consider the trade-offs between speed and area to generate a fully customized cell which meets their specific device requirements.

EMBEDDED FUNCTIONS

Embedded function are available for high density, high performance SPRAM, DPRAM, ROM and FIFO. These are complimented by a group of embedded megafunctions which initially consist of a Triple 8-bit DAC, Graphics RAM, Clock Multiplier PLL and Frequency Synthesis PLL.

DESIGN FOR TESTABILITY

The time and cost for ASIC testing increases exponentially as the complexity and size of the ASIC grows. Using a design for testability methodology allows large, more complex ASICs to be efficiently and economically tested.

ISB28000 supports the JTAG boundary Scan and edge level sensitive design scan by providing the necessary macrocells.Scan testing aids device testability by permitting access to internal nodes without requiring a separate external connection for each node accessed. Testability is assured at device level with the close coupling of LSSD latch elements, Automatic Test Pattern Generation (ATPG) and high pattern depth tester architecture. At system level, SGS-THOMSON fully supports IEEE 1149.1, within the array of each cell array member. Two types of scan cells are provided by the ISB28000 Series library. They are FDxS/FJKxS cells which are edge sensitive and LSxx cells which are truly LSSD cells.

PACKAGE AVAILABILITY

The ISB28000 Series is designed to be especially suitable for high volume surface mount applications, from 28 pin plastic leaded chip carriers (PLCC) up to 160 pin metric quad flatpacks (MQFP) with over 300 pin MQFPs in development. Pin counts forthrough board mounting range up to 299. For higher pin counts the range is compatible with the industry standard JEDEC and EIA-J Guardring Quad Flatpack (GQFP) with pin counts from 186 to 306.

The diversity in pin count and package style gives the designer the opportunity to find the best compromise for system size, cost and performance requirements.

All packages for the military market are hermetically sealed to meet MIL-STD-883 Method. Prototypes are developed in ceramic packages for fast turnaround evaluation.

DESIGN ENVIRONMENT

Several interface levels arepossible between SGS-THOMSON and the customer in the undertaking of an ASIC design. The four levels of interface are shown in Figure 6. Level 1 is characterized by SGS-THOMSON receiving the system specification and taking the design through to validation and fabrication. At Level 2 interface the designer supplies a complete logic design implemented in a standard generic logic family. SGS-THOMSON then

takes the design through to layout, validation and fabrication.

Level 3 is the most common and preferred interface level. Logic capture and pre-layout simulation are performed by the designer using a SGS-THOM-SON supported design kit. The design is then taken through layout, validation and fabrication by SGS-THOMSON

The SGS-THOMSON design system validates all designs before fabrication. Design kits are provided that allow schematic entry via Mentor Graphis, Cadence Amadeus and Valid Logic. Simula-tion is supported on Cadence Amadeus and Mentor Graphics. Full support is also provided forCadence Verilog,VHDL-XL and SystemHilosimulators. Figure 7 shows the SGS-THOMSON Design Flow.

Figure 6. Customer SGS-THOMSON Interface Levels

ISB35_VC

Figure 7. SGS-THOMSON Design-Flow

ABSOLUTE MAXIMUM RATINGS (Note 1)

Note 1: Referenced to V_{SS}. Stresses above those listed under "absolute maximum ratings" may cause permanent damage to the device. This is a stress rating only and functional operation of the device at these or any other conditions above those indicated in the operation sections of this specification is not implied. Exposure to absolute maximum rating conditions for extended periods may affect the device reliability.

RECOMMENDED DC OPERATING CONDITIONS

DC ELECTRICAL CHARACTERISTICS Across Temperature Range (Note 1)

Notes 1. Commercial 0 to 70°C, $V_{DD} = 5 V \pm 5\%$.

Industrial -40 to 85°C, $V_{DD} = 5 V \pm 10\%$.

2. Adherence to rules in Power Requirements section required.

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APPENDIX - MACROCELL LIBRARY

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